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## **【531】 High-resolution, low-temperature ARPES at SIS-ULTRA**

*Tuesday, June 28, 2022 7:00 PM (1 minute)*

Developing and understanding novel quantum materials pushes angle-resolved photoemission (ARPES) into new frontiers of resolution and extreme conditions. ULTRA endstation at the SIS beamline of the Swiss Light Source is a novel system for high-resolution ARPES at temperatures down to 4 K. With independent 6-axis control, minimal thermal drift, deflector scanning, and easy alignment, ULTRA is not only powerful, but also user-friendly and geared toward high-throughput spectroscopy. A newly added instrument cluster for *in situ* film growth and scanning probe techniques enables cutting-edge investigations of oxide films and heterostructures. I will summarize the present status of ULTRA, highlight recent science, and discuss future plans, including integration into SLS 2.0.

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